INTERFERENCE

ENOVIA VPM Interference Management

ENOVIA® VPM Interference Management improves design quality, enhances time to market, and keeps costs in control by detecting, tracking, and managing interferences on complex and large digital mockups.

Key Benefits

- Avoid costly mistakes and lost productivity by performing regular design interference checks on complex digital mockups to identify errors earlier in the product-development process
- Improve design product quality by automating interference verifications, tracking and resolution, ensuring more efficient management of errors and design changes
- Optimize CPU performance while still handling large data volumes, improving productivity by allowing batch processing for interference computations
- Enhance decision-making with access to accurate, real-time product data, when performing interference computation

Product Overview

One of the biggest product-development challenges for companies who design complex, multi-part products with large volumes of data is discovering design errors earlier in the product-development process. Companies typically conduct regular design interference checks, but these can be time-consuming and resource-intensive; often providing no formal or standard process for design review and validation. Many times, digital mockups are built using data gathered from multiple repositories that rely on inefficient tools for accessing accurate and timely data. This imposes the great risk of too many design errors being discovered late in the product-development process, impeding the ability for companies to make intelligent design decisions with the assurance that they are using the most up-to-date data, and resulting in late-to-market products and unnecessary cost hikes.

ENOVIA VPM Interference Management provides product synthesis experts with the capabilities to detect interferences efficiently on complex and large digital mockups. Users can detect potential clearance, contact, and clash defects by selecting a specific design context and launching computations. The product allows users to define interference computation specifications and store the results in the Dassault Systèmes V6 database for future reuse. Users can leverage the ENOVIA® 3DLive™ user experience to search, navigate, and collaborate on interferences.

Product Highlights

Enable Product Synthesis Experts to Perform Global Interferences Detection on Digital Mockups

Users can set up a complete environment, including a design context built from filters on product configurations, volume, and other attributes (including owner name, role and maturity) and interference computation specifications. Once identified, users can search and navigate the different issues using the 3DLive user experience and analyze in context.

Automate Interference Verifications, Tracking, and Resolution for Improved Design Product Quality

ENOVIA VPM Interference Management allows users to prepare digital mockup data for formal design review and an analysis of the errors found. In a second step, users can assign these errors to teams and designers to perform the required modifications. Designers retrieve the errors using ENOVIA® VPM Interference Check.

Handle Large Volumes of Data With Optimized Performance

When dealing with large assemblies, ENOVIA VPM Interference Management allows users to launch computations in batch mode and allocate separate processes for an optimized usage of available resources. The batch mode enables users to optimize the CPU resources of a company by running computations during downtime. The separated process enables users to work optimally in their V6 session while interferences are computed with large memory spaces.

Ensure a Global End-to End Process

ENOVIA VPM Interference Management allows you to more effectively manage the retrieval, analysis, and correction of errors, enabling you to make more intelligent design and development decisions and resulting in improved product quality. And with ENOVIA VPM Interference Check, you can enhance designers' ability to interactively identify errors and check the consistency of their design while staying in their authoring environment (CATIA®, DELMIA®).

ENOVIA Compliancy

When ENOVIA VPM Interference Management is deployed along with ENOVIA® VPM Team Central™ or ENOVIA® VPM Central™ using the available ENOVIA Rapid Application Configured Environment (R.A.C.E)., the applications can be used immediately in production. This eliminates the need for specific customizations and reduces the time and effort for enterprise deployments.

The Role of ENOVIA V6 and PLM 2.0

ENOVIA VPM Interference Management supports PLM 2.0, product lifecycle management online for everyone, and the ENOVIA V6 values: global collaboration innovation, single PLM platform for intellectual property (IP) management, online creation and collaboration, ready to use PLM business processes, and lower cost of ownership.

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